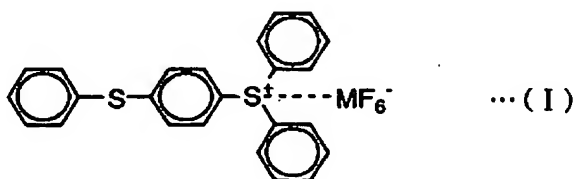


CLAIMS

1. A resin composition for stereolithography, which is an actinic radiation-curable resin composition comprising:

- a cationic-polymerizable organic compound;
- a radical-polymerizable organic compound;
- a photo initiator for cationic polymerization; and
- a photo initiator for radical polymerization,

wherein the photo initiator for cationic polymerization comprises a compound represented by the following formula (I), the compound having a purity of 80% or higher:



wherein M represents an antimony atom or a phosphorus atom; and the broken line between S^+ and MF_6^- represents an ionic bond.

2. The resin composition for stereolithography as claimed in claim 1, wherein the purity of the compound represented by the formula (I) is 90% or higher.

3. The resin composition for stereolithography as claimed in claim 1 or 2, wherein the purity of the compound represented by the formula (I) is 95% or higher.

4. The resin composition for stereolithography as claimed in any of claims 1 to 3, wherein M in the compound represented by the formula (I) is an antimony atom.

5. The resin composition for stereolithography as claimed in any of claims 1 to 4, wherein the cationic-polymerizable organic compound comprises at least one compound

having an epoxy group.

6. The resin composition for stereolithography as claimed in any of claims 1 to 5, wherein the radical-polymerizable organic compound comprises at least one compound having a (meth)acryl group.

7. The resin composition for stereolithography as claimed in any of claims 1 to 6, which comprises an oxetane compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.

8. The resin composition for stereolithography as claimed in any of claims 1 to 7, which comprises a polyalkylene ether compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.